

Industrial Instruments General Catalogue



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The highly cost-effective SMZ series offer outstanding optical performance, flexible system expandability, and superb operability.

Parallel Optics Type SMZ1270 SMZ25 SMZ18 SMZ800N SMZ1270i Zoom Ratio 12.7:1 25:1 18:1 8:1 $0.75 - 13.5 \times$ $0.63 - 15.75 \times$ $0.63 - 8 \times$ $1-8 \times$ Zoom Range Total $3.15 - 945 \times$ 3.75-810× $3.15 - 480 \times$ 5-480× Magnification*1 (Standard combination*2) $(6.3-157.5\times)$ $(7.5-135\times)$ $(6.3 - 80 \times)$ $(10-80 \times)$ 60 mm 60 mm 70 mm 78 mm Camera ✓ : Available / — : Not available

Greenough Type						
	SMZ745 SMZ745T		SMZ SMZ			SMZ-2
Zoom Ratio	7.5 : 1		4.4 : 1	4.3 : 1		5 : 1
Zoom Range	0.67–5×		0.8 –3.5×	0.7 –3×		0.8-4×
Total Magnification*1 (Standard combination*2)	3.35–300× (6.7–50×)		4–70× (8–35×)			4–120× (8–40×)
WD *3	115 mm		100 mm			77.5 mm
Camera	✓ (SMZ745T only)		<u>—</u>			
						✓ : Available / — : Not available

^{*1:} Depending on combination of Eyepiece and Objective lens. *2: Combination of Eyepiece 10x and Objective lens 10x. *3: Objective lens 1x or no Auxiliary lens.

Industrial Microscopes

Nikon's Industrial Microscopes utilize the CFI60-2 optical systems, highly evaluated for its unique concept of high NA combined with long WD.

Upright Microscopes (General model)

LV100ND LV100NDA

Model offers various observation methods with reflected/transmitted illumination.



LV150N LV150NA LV150NL*

Stand and illumination units are selectable according to observation methods and purpose of use.



Observation Method

	BF	DF	DIC	FL	POL	2-Beam	Ph-C
EPI	V	V	V	V	V	V	_
EPI (LED)	V	V	V	_	Δ	_	_
DIA	V	V	V		V		V

✓ : Available / — : Not available / △: Simple polarizing observation

Illuminator

Episcopic / Diascopic

Stage

- 3×2 Stage (stroke 75×50mm)
- 6×4 Stage (stroke 150×100mm)
- *See the "LV-N Series" brochure for other compatible stages.

	BF	DF	DIC	FL	POL	2-Beam
EPI	~	V	~	V	V	~
EPI (LED)	~	~	~	_	Δ	_

- ✓ : Available / : Not available / Δ: Simple polarizing observation
- Episcopic
- 3×2 Stage (stroke 75×50mm)
- 6×6 Stage (stroke 150×150mm)
- *See the "LV-N Series" brochure for other compatible stages.

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast FL: Fluorescence POL: Polarizing 2-Beam: Two-Beam Interferometry Ph-C: Phase-Contrast *Only BF, DIC, and S-POL are available for LV150NL

Upright Microscopes (Large-sized stage model)

L200N L200ND

Stage with stroke 200×200mm is available. Suitable for ø200mm wafer observation.



L300ND

Stage with stroke 350×300mm is available.
Suitable for ø300mm wafer observation.



Observation Method

	BF	DF	DIC	S-POL	FL
EPI	V	V	~	V	v *
DIA	v *	_	_	_	

*L200ND only

✓ : Available / — : Not available

Illuminator

- L200N : Episcopic
- L200ND : Episcopic / Diascopic

Stage

8×8 Stage (stroke: 200×200mm)

	BF	DF	DIC	S-POL	FL
EPI	V	V	V	V	V
DIA	V *	_	_	_	_

*L300ND only

✓ : Available / — : Not available

- L300N : Episcopic
- L300ND : Episcopic / Diascopic
- 14×12 Stage (stroke: 350×300mm)

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Inverted Metallurgical Microscopes

MA100N

MA100N is compact, inverted microscopes designed for brightfield and simple polarizing observations.



MA200

With its unique, solid-box structure. the MA200 offers high stability, durability, and a smaller footprint than conventional models.

• Episcopic / Diascopic



Observation
Method

Stage

	BF	DF	S-POL	DIC	FL
EPI	V	_	V	_	

✓ : Available / — : Not available *Dedicated reflected illumination models.

✓ : Available / — : Not available △: Only available with Halogen Lamp and Fiber Illumination

S-POL

*DIA illuminator is available for transmitted light observation.

- Episcopic Illuminator
 - MA-SR-N Rectangular 3-plate Stage N (stroke 50×50mm)
 - MA-SP-N Plain Stage N
 - TS2-S-SM Mechanical Stage CH (stroke 126×78mm)
 - *Please use in combination with MA-SP-N Plain stage N.

• MA2-SR Mechanical Stage (stroke 50×50mm)

BF: Brightfield DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Polarizing Microscopes

LV100NPOL

Outstanding optical performance, perfect for a wide variety of imaging applications and polarizing techniques.



Ci POL

Compact polarizing microscope that balances optical performance and ease of use.



Observation Method

	BF	POL
EPI	V	✓
DIA	V	✓
		· Available / — · Not available

Illuminator

• Episcopic/ Diascopic

Stage

• High precision rotating stage for polarizing observation

	BF	POL
EPI	~	V
DIA	~	V
		: Available / : Not available

• Episcopic/ Diascopic

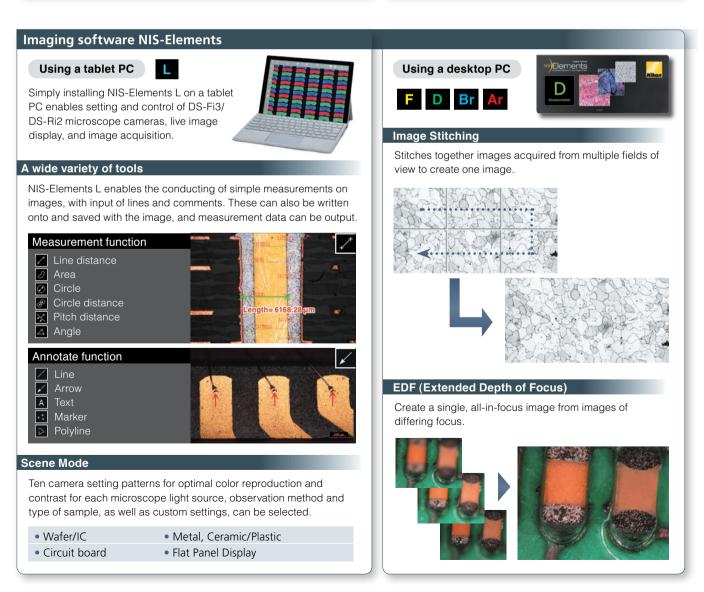
· Rotating stage with stage clamp

BF: Brightfield POL: Polarizing DF: Darkfield DIC: Differential Interference Contrast S-POL: Simple Polarizing FL: Fluorescence

Digital Sight Series

The lineup allows you to select a suitable camera for each sample and observation method.





Optical Interferometric Microscope Systems BW-S500/BW-D500 Series

Nikon's proprietary scanning-type optical interference measurement technology achieves 1 pm height resolution. Nikon offers variety application, lustrous surfaces, such as silicon wafer, glass and metallic deposition surfaces.

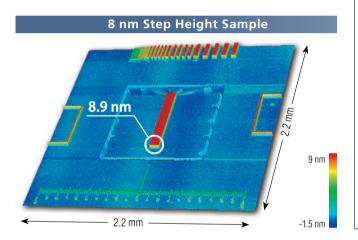
	High Speed Model	High Pixel Resolution Model			
	BW-D500 Series	BW-S500 Series			
Height Resolution (algorithm)	1 pm				
Step Height Measurement Reproducibility	σ: 8 nm (8 μm Step height measurement)				
Number of Pixels	510×510	2,046×2,046	1,022×1,022		
Height Measurement Time	2 s 19 s 8 s (10 µm scan) (10 µm scan) (10 µm scan)				
Field of view	< 2,015×2,015 μm*	< 4,458×	4,448 µm*		



High Accuracy and Repeatability

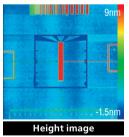
The BW-S500/BW-D500 series is calibrated by an 8 nm or 8 µm VLSI Step Height Standards sample, certified by the NIST. Achieves extremely high accuracy and repeatability as a height measurement system.

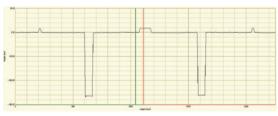




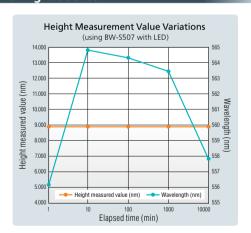
Measured value unsusceptible to variation of central wavelength of light source

With Nikon's proprietary technology, measurement values with the BW-S500/ BW-D500 series are independent of central wavelength of light source. Measurements can be done immediately after switching on illumination source.

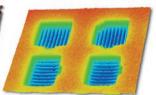


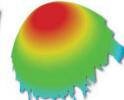


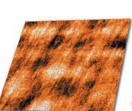
Calibrated Value (NIST): 8.9 nm ±0.6 nm Average Value by BW-S507: 8.906 nm(10 times/\sigma 0.031 nm)

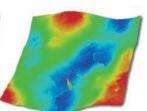












Polished ceramic surface

Metal Etching Surface

Lens

Glass

Glossy paper

^{*} The range can be extended by changing the relay lens or by stitching.

Nikon's CFI60-2/CFI60 optical systems are highly evaluated for its unique concept of high NA combined with long working distance. These lenses have further evolved to achieve the apex in long working distance, correct chromatic aberration, and optimized lens weight.









BF: Brightfield DF: Darkfield POL: Polarizing S-POL: Simple Polarizing DIC: Differential Interference Contrast UV-FL: UV Fluorescence FL: EPI Fluorescence

	Model	Magnification	NA	WD (mm)	BF	DF	POL	S-POL	DIC	UV-FL	FL
	T Plan EPI	1×	0.03	3.8	~	_	_	_	_	_	
	Plan (Semi-apochromat)	2.5×	0.075	6.5				_	_	_	<u> </u>
	TU Plan Fluor EPI	5×	0.15	23.5	~	_	_	~	∨ A	~	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5				~	∨ A	~	~
		20×	0.45	4.5	\ \	_	_	~	∨ A	~	~
		50×	0.8	1.0		_	_	~	∨ A	~	~
		100×	0.9	1.0	\ \	_	_	~	∨ A	~	~
	TU Plan Apo EPI	50×	0.8	2.0	~			~	∨ A		~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0	\ \			~	∨ A	_	~
		150×	0.9	1.5	~		_	~	∨ A	_	~
	TU Plan Fluor EPI P	5×	0.15	23.5	~		~	~	∨ A	~	~
	Polarizing Universal Plan Fluor (Semi-apochromat)	10×	0.3	17.5			~	~	∨ A	~	~
		20×	0.45	4.5	\ \		~	~	∨ A	~	~
		50×	0.8	1.0			~	~	∨ A	~	~
		100×	0.9	1.0	\ \		~	~	∨ A	~	~
CFI60-2	TU Plan EPI ELWD	20×	0.4	19.0	~	_		~	∨B	_	~
CF160-Z	Long Working Distance Universal Plan	50×	0.6	11.0				~	∨B		~
	(Semi-apochromat)	100×	0.8	4.5			_	~	∨B	_	~
	T Plan EPI SLWD	10×	0.2	37.0	~	_	_	_	_	_	~
	Super Long Working Distance Plan (Semi-apochromat)	20×	0.3	30.0		_		_	_	_	~
	(Semi-apochromat)	50×	0.4	22.0		<u> </u>		_	_	_	~
		100×	0.6	10.0	\ \		_	_	_	_	~
	TU Plan Fluor BD	5×	0.15	18.0	~	~	_	~	∨ A	~	~
	Universal Plan Fluor (Semi-apochromat)	10×	0.3	15.0	\ \	V		~	∨ A	~	~
		20×	0.45	4.5		~		~	∨ A	~	~
		50×	0.8	1.0	\ \	/		~	∨ A	~	~
		100×	0.9	1.0	~	~	_	~	∨ A	~	~
	TU Plan Apo BD	50×	0.8	2.0	~	~		~	∨ A		~
	Universal Plan Apo (Apochromat)	100×	0.9	2.0		~		~	∨ A	_	~
		150×	0.9	1.5	~	~	_	~	∨ A	_	~
	TU Plan BD ELWD	20×	0.4	19.0	~	~		~	∨B	_	~
	Long Working Distance Universal plan (Semi-apochromat)	50×	0.6	11.0	~	~		~	∨B	<u> </u>	~
	(Semi-apocinomat)	100×	0.8	4.5	~	~	_	~	∨B	_	~
	L Plan EPI (Achromat)	40×	0.65	1.0	~	_	_	_	_	_	~
	LU Plan Apo EPI / Universal Plan Apo (Apochromat)	150×	0.95	0.3	~	_	_	~	∨ A	_	~
	L Plan EPI CR	20×	0.45	10.9–10.0	~			_		_	~
	LCD Substrate Inspection Plan (Achromat)	50×	0.7	3.9–3.0				_	_	_	~
	*Offers valid while supplies last	100×	0.85	1.2-0.85				_	_		~
		100×	0.85	1.3-0.95	~	_	_	_	1	_	~
	LE Plan EPI (Achromat)	5×	0.1	31	~	_			_		~
CFI ₆₀		10×	0.25	13				_	_	_	~
CI 100		20×	0.4	3.6		_		_	_		~
		50×	0.75	0.5		_	_	_	_	_	~
		100×	0.9	0.31	~	_	_	_	_	_	~
	LE Plan BD (Achromat)	5×	0.1	18	~	~		_	_	_	~
		10×	0.25	13		~		_	_		~
		20×	0.4	3.6		~	_	_	_	_	~
		50×	0.75	0.5	V	V	_	_	_	_	~

✓ : Available / — : Not available *A: Set prism position at A / B: Set prism position at B

For Incorporation into Microscopes

Modular Focusing Units

IM-4, LV-IM/LV-IMA, LV-FM/LV-FMA

Suitable for incorporating into systems, these focusing units enable the mounting of a universal illuminator and a motorized nosepiece.

	IM-4	LV-IM/LV-IMA	LV-FM/LV-FMA
Туре	Manual	Manual / Motorized	Manual / Motorized
Vertical Stroke	30 mm	30/20 mm	30/20 mm



Dynamic Auto-Focus Unit

LV-DAF

Hybrid Auto-focus features a wide focus range and fast tracking ability. A wide range of observation methods are supported, including brightfield, darkfield, and DIC. Reflective and transparent samples can both be observed.

*Not compatible with NIS-Elements imaging software

Detection System	Split Projection System/ Contrast Detection System					
AF Light Source Near Infrared LED (λ=770 nm)						
Focal Time	within 0.7 sec (Obj. lens: 20×, Distance from focal position: 200 μm)					
Observation	Brightfield, Darkfield, Polarizing, DIC					



Compact Reflected Microscopes

CM Series

Ultra-compact reflected microscopes designed for integration into production lines to observe on monitors.



	CM-5A	CM-10A/CM-10L	CM-20A/CM-20L	CM-30A2/CM-30L2		
Camera Mount	C-mount (ENG-mount possible with option)					
Tube Lens Magnification	_	1×	0.5×	1×		
Compatible Objectives	A series: CF	FIC EPI Plan objectives / L se	eries: CFI60-2/ CFI60 EPI Pla	n objectives		
Illumination Optical System	Koehler illumination (high-quality telecentric illumination)					
Attachment Surfaces	3 4					

Wafer Loaders

Nikon's proprietary technology ensures reliable loading of ultra-thin 100 μ m wafers. The NWL 200 series achieve highly reliable loading, suitable for inspection of next-generation semiconductors.

	Diameter	ø200 mm / ø150 mm			
Wafer	Thickness (standard)	300 um			
	Thickness (option)	300–100 um			
Surface	, back side macro inspection	\checkmark			

NWL200 Series



Wide variety of stage strokes and magnifications are available for various customer requirements.

Main Body (Type / Stage Stroke)





High-precision Model VMZ-H Model VMZ-H3030
NEXIV VMZ-H3030

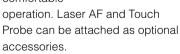
Model	Wide FOV				High-precision		
XY Stroke	250×200 mm	450×400 mm	650×550 mm	300×200 mm	450×400 mm	650×550 mm	300×300 mm
Wide FOV Head	✓	✓	✓	✓	✓	~	
Standard Head				~	~	~	✓
High-Magnification Head				~	~	~	✓
Z-axis Stroke	200 mm	200 mm	200 mm	200 mm	200 mm	200 mm	150 mm
Max. guaranteed loading capacity	15 kg	20 kg	30 kg	20 kg	40 kg	50 kg	30 kg
Maximum permissible error (Eux, Mpe Euy, Mpe)	2+8 <i>L</i> /1000 μm	2+6 <i>L</i> /10	000 µm		0.6+2 <i>L</i> /1000 μm		
Maximum permissible error (Euz, MPE)	3+ <i>L</i> /50 μm	3+ <i>L</i> /10	00 μm		0.9+ <i>L</i> /150 μm		

L = Length in mm

Zoom Heads

Type A

Wide FOV and long working distance enables comfortable



*Touch Probe is an option only for VMA series.

Type 1-4

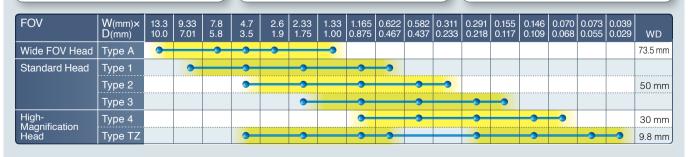
Equipped with top, bottom, and oblique ring

lights with adjustable angles. TTL (Through the Lens) Laser AF is a standard tool that can scan surfaces at 1000 points/second.

Type TZ

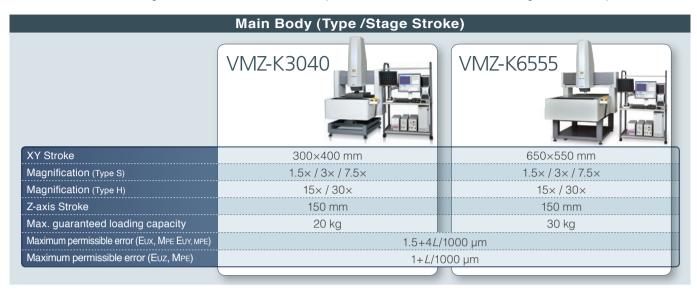
Equipped with 1-120x ultra high zoom ratio with 8 steps. Suitable for

measurements of small targets up to several micrometers.



Confocal NEXIV Series

Simultaneous wide-area height measurements with confocal optics and 2D measurement with 15× brightfield zoom optics.



	Zoom Heads																
FOV	W(mm)× D(mm)	8 6	4 3	2.0 1.5	1.6 1.2	1.26 0.95	1.00 0.75	0.8 0.6	0.63 0.47	0.53 0.40	0.4 0.3	0.27 0.20	0.20 0.15	0.11 0.08	0.100 0.074	0.05 0.04	WD
Type S	1.5×	•	•	•			-			-							24mm
	3×		-	-			-			-		-					24mm
	7.5×				•			-			-		-	-			5mm
Туре Н	15×					•		-			-		-		-		20mm
	30×								•		-		-		-	-	5mm
													Brigh	tfield	Confo	cal/Briç	htfield

Confocal NEXIV incorporates confocal optics for fast and accurate evaluation of fine three-dimensional geometries.

Confocal Optics are designed for wide FOV height measurement.

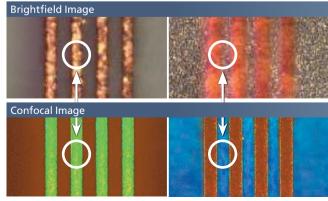
Brightfield Contour 3D view

High Contrast and Multileveled Sample (PCBs)

Brightfield observation can sometimes be difficult due to blurred lines along sample structure. These lines can be clearly observed and measured using Confocal optics.



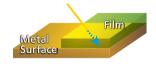
SEM image

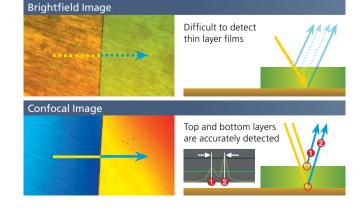


Top detected Bottom detect

Thin Transparent Samples (Metal Surface Film / Semiconductor Resist)

Top layers of both thin transparent film and metal surface can be easily detected using Confocal optics.





Measuring Microscopes

Focused on high-precision and easy operability, a wide range of MM-products are available.

Compact Model MM-200

Basic Model
MM-400
5



	50×50 mm / 5 kg	✓	✓	✓	
	100×100 mm / 15 kg	_	✓	✓	
Stage Size/ Loading	150×100 mm / 15 kg	_	V	✓	
Capacity	200×150 mm / 20 kg	_	_	✓	
	250×150 mm / 20 kg	_	_	✓	
	300×200 mm / 20 kg	_	_	✓	
Max. Sample	Height	110 mm	150 mm	200 mm	
Optical	Monocular	✓	✓	_	
Head	Binocular	_	✓	✓	
X-Y-Z	2-axis	✓	✓	✓	
X-1-Z	3-axis	_	✓	✓	
CCD		√ *	✓	✓	
Obj. Magnific	ation	1×/3×/5×/10×	1×/3×/5×/10×/20×/50×/100×		

^{*}For simple video head only

✓ : Available / — : Not available

MM Type

With Nikon's optical technology and highly precise stages, high-precision measurement can be achieved.



Universal Type

Offers a line-up compatible with dimensional measurement and various observation methods.



High-Precision Stages

The coarse/fine changeover lever and the RESET and SEND buttons are located near the X- and Y-axis knobs.







X-axis Knob



Y-axis Knob

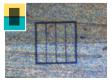
Focusing Aid (FA)

The Split-Prism FA delivers sharp patterns to allow accurate focusing during Z-axis measurements.

FA patterns are clearly visible because they are split vertically.









Front Focus

Focused

Rear Focus

Profile Projectors

V-12B

Nikon's profile projectors apply the principles of optics to the inspection of manufactured parts by projecting magnified silhouettes on a screen.

Desktop Model

Large-Screen	Model

V-20B



	50×50 mm / 5 kg	√	✓			
	100×100 mm / 15 kg	✓	\checkmark			
Stage Size/ Loading	150×100 mm / 15 kg	✓	✓			
Capacity	200×150 mm /20 kg	✓	✓			
	250×150 mm / 20 kg	✓	✓			
	225×100 mm / 30 kg	-	_			
Max. Sample	e Height	100 mm*²	150 mm			
Screen		305 mm	500 mm			
Image		Erect	Inverted			
Projection	Magnification	5×/10×/20×/25×/50×/100×/200×	5×/10×/20×/50×/100×			
Lens	FOV (with 10× lens)*1	30.5 mm	50 mm			
Digital Protractor		\checkmark	✓			
Digital Count	ter	✓	✓			

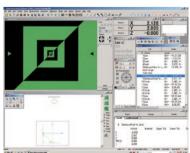
- *1: Actual FOV = Effective diameter of screen / Lens magnification
- *2: Maximum sample height is 70 mm when 200×150 mm stage is installed.

✓ : Available / — : Not available

Data Processing Systems for Measuring Microscopes and Profile Projectors

Data Processing Software E-MAX

Provides the user with various advanced measurements and processing functions. Automated edge detection with sub-pixel processing enables more precise and repeatable measurements.



Data Processor

DP-E1A



Effectively used with a measuring microscope / profile projector, it quickly calculates and processes measurement data. Feature Oriented Operation of the DP-E1A allows the user to conduct measurements with the graphics, providing a seamless measuring environment.

> 9.8813 -1.2534-0.0026

Connected with profile projector, retrofit counter and DP units are required.

Connected with profile

functions only

projector, data processing

Autocollimators

Autocollimator is an easy-to-use but precise metrology instrument for angularity, parallelism, perpendicularity, straightness of precision components machine guideway and many other applications.

Brightfield Type

6B-LED



Utilizes hallmark Nikon optics to illuminate surface details.

Darkfield Type

6D-LED



Optimal for measuring small, flat mirrors.



Observation Method
Readout System
Measuring Range

Minimum Range

6B-LED: Brightfield, 6D-LED: Darkfield
Adjustment in viewfield and reading on micrometer
30 minutes of arc (both vertical and horizontal axes)

0.5 seconds of arc

Plane Mirror C

Both sides are perfectly parallel, permitting its use as a reference for non-reflective surface. Also useful for measuring extremely small angles where a smaller mirror is desirable. *Wooden case provided.



Outer Diameter	30 mm
Thickness	12 mm
Parallelism	2 seconds of arc

LED Illuminator AC-L1

LED illumination unit for retrofitting onto Autocollimator 6B/6D illumination unit.



Power Source

AA batteries×2, AC adaptor

DIGIMICRO

With built-in photoelectric digital length measuring systems, DIGIMICRO offers flawless contact measurements of dimension, thickness, and depth.

Main unit MF-1001 + Counter MFC-101A + Stand MS-21







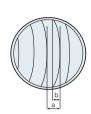
Main Unit	MF-1001	MF-501	MH-15M
Measuring Range	0–100 mm	0–50 mm	0–15 mm
Accuracy (20°C)	3 μm	1 µm	0.7 μm
Measuring Force	Downward direction 1.225 to 1.813N (variable to about 0.441N), lateral 0.637 to 1.225N	Downward direction 1.127 to 1.617N (variable to about 0.294N), lateral 0.637 to 1.225N	Upward direction 0.245N, downward 0.637N, lateral 0.441N *With lifting release
Operating Temperature	0 to 40°C		

Optical Flat / Optical Parallel / Standard 300 mm Scale

Optical Flat

The optical flat is used to check the flatness level of a surface provided with mirror-smooth finish.

Flatness level can be measured by observing interference fringes by placing the optical flat in contact with the sample.





Diameter	Glass (ø60 mm)	Glass (ø130 mm)
Thickness	15 mm	27 mm
Flatness	0.1 μm	0.1 μm

Optical Parallel

Both planes of the optical parallel have been precisely finished flat and parallel.

It is used to check the flatness and parallel levels of a sample by observing

interference fringes by placing the optical parallel in contact with the sample.



Diameter	30 mm
Thickness	12 mm / 12.12 mm / 12.25 mm / 12.37 mm
Flatness	within 0.1 μm
Parallelism	within 0.2 μm

^{*}Optical flats and parallels with greater precision are available by custom orders.

Standard 300mm Scale

Gauges stage travel accuracy up to 300 mm. Both 10 mm-interval sensor patterns and calibrations are provided. $\frac{1}{2} \frac{1}{2} \frac{1}{$

Made of the glass with low coefficient of thermal expansion, for minimizing thermal influence.

*Within 1 µm against compensation values.

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TO ENSURE CORRECT USAGE, READ THE CORRESPONDING MANUALS CAREFULLY BEFORE USING THE EQUIPMENT.



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